



## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Deo, Duy Vu Nguyen Hou, Chien-Chou; et al. Applicant: Examiner: 10/600,377 Art Unit: 1765 Serial No.: Our Ref: B-5130 621033-6 Filed: June 20, 2003 November 22, 2005 "METHOD OF ETCHING UNIFORM For: Date: SILICON LAYER" Amendment and Response Re:

## **AMENDMENT AND RESPONSE**

Mail Stop RCE Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In reply to the final Office Action mailed on August 23, 2005, a response to which is due no later than

## November 23, 2005,

the Applicant submits this amendment pursuant to 37 C.F.R. 1.114 together with a Request for Continued Examination. Please amend the above-identified application as described below and consider the following remarks. All amendments and remarks herein are made without prejudice.

A Request for Continued Examination (RCE), a fee form, and requisite fee are included with this response.

Amendments to the Claims are reflected in the listing of claims that begins on page 2 of this paper.

Remarks/Arguments begin on page 5 of this paper.